CLAIMS

What is claimed is:

1. A method of cleaning a process chamber, comprising the steps of:

providing a gas mixture comprising nitrous oxide and nitrogen trifloride in a nitrous oxide:nitrogen trifluoride volume ratio of at least about 0.2;

introducing said gas mixture into the process chamber; and

generating a plasma from said gas mixture.

- 2. The method of claim 1 further comprising the step of providing an inert carrier gas in said gas mixture.
- 3. The method of claim 1 wherein said nitrous oxide:nitrogen trifluoride volume ratio is from at least about 0.2 to about 0.8.
- 4. The method of claim 3 further comprising the step of providing an inert carrier gas in said gas mixture.
- 5. The method of claim 2 wherein said inert carrier gas comprises argon.

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- 6. The method of claim 5 wherein said nitrous oxide:nitrogen trifluoride volume ratio is from at least about 0.2 to about 0.8.
- 7. The method of claim 2 wherein said inert carrier gas comprises helium.
- 8. The method of claim 7 wherein said nitrous oxide:nitrogen trifluoride volume ratio is from at least about 0.2 to about 0.8.
- 9. A method of cleaning a process chamber, comprising the steps of:

providing a gas mixture comprising nitrous oxide and nitrogen trifloride in a nitrous oxide:nitrogen trifluoride volume ratio of at least about 0.8;

introducing said gas mixture into the process chamber; and

generating a plasma from said gas mixture.

10. The method of claim 9 further comprising the step of providing an inert carrier gas in said gas mixture.

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- 11. The method of claim 10 wherein said inert carrier gas comprises argon.
- 12. The method of claim 10 wherein said inert carrier gas comprises helium.
- 13. A method of expediting cleaning of a process chamber using nitrogen trifluoride, comprising the steps of:

forming a gas mixture by adding nitrous oxide to the nitrogen trifluoride in a nitrous oxide:nitrogen trifluoride volume ratio of at least about 0.2;

introducing said gas mixture into the process chamber; and

forming nitric oxide radicals and fluoride radicals in the process chamber by generating a plasma from said gas mixture.

- 14. The method of claim 13 further comprising the step of providing an inert carrier gas in said gas mixture.
- 15. The method of claim 13 wherein said nitrous oxide:nitrogen trifluoride volume ratio is from at least about 0.2 to about 0.8.

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- 16. The method of claim 15 further comprising the step of providing an inert carrier gas in said gas mixture.
- 17. The method of claim 13 wherein said nitrous oxide:nitrogen trifluoride volume ratio is at least about 0.8.
- 18. The method of claim 17 further comprising the step of providing an inert carrier gas in said gas mixture.
- 19. The method of claim 18 wherein said inert carrier gas comprises argon.
- 20. The method of claim 18 wherein said inert carrier gas comprises helium.